



	<b>Experiment title: Mechanical properties of Ta under high pressure by single-crystal X-Ray diffraction</b>	<b>Experiment number:</b> HS-1361
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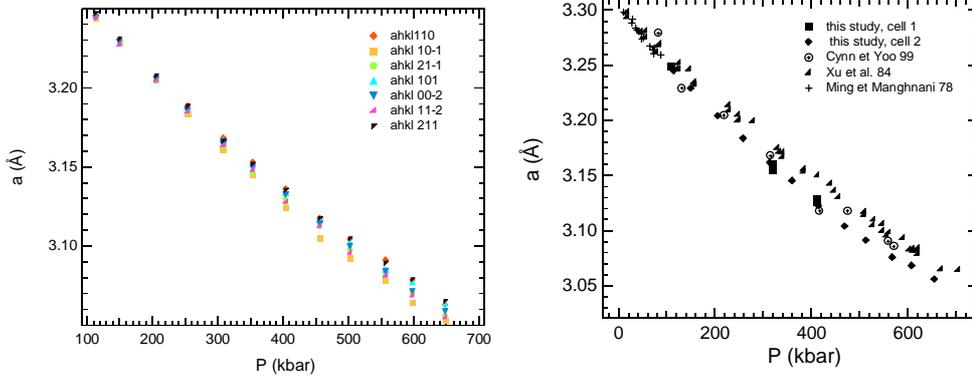
**Report:**

White beam single crystal X-Ray diffraction on Tantalum samples has been performed up to 65 GPa. The samples were deformed (a) under quasi-hydrostatic conditions (embedded in helium pressure medium), cell 1; (b) under uniaxial stress (sample embedded in helium but in contact with the diamond anvils), cell 2. This experiment had two goals: (1) the determination of a reference equation of state (EoS) under ultra-high pressure and ambient temperature; (2) the determination of pressure effect on the maximum deviatoric stress sustained by the sample before plastic yielding (i.e. the yield stress).

**Experimental method:** Lattice parameters values of several planes of Ta (bcc crystal), with different orientations towards the compression axis, have been measured for cells 1 and 2 (figure 1). From these values, the hydrostatic lattice parameter and the deviatoric stress  $\tau = \sigma_3 - \sigma_1$  ( $\sigma_3$  and  $\sigma_1$  are respectively the principal stresses parallel and perpendicular to the compression axis) have been calculated for each pressure step. For cell 2, approximate plastic deformation  $\epsilon^P$  (function of  $t$ , the thickness of the sample) has been measured by interferometric method in the pressure transmitting medium (helium).

**(1) EoS of tantalum to 65 GPa:**

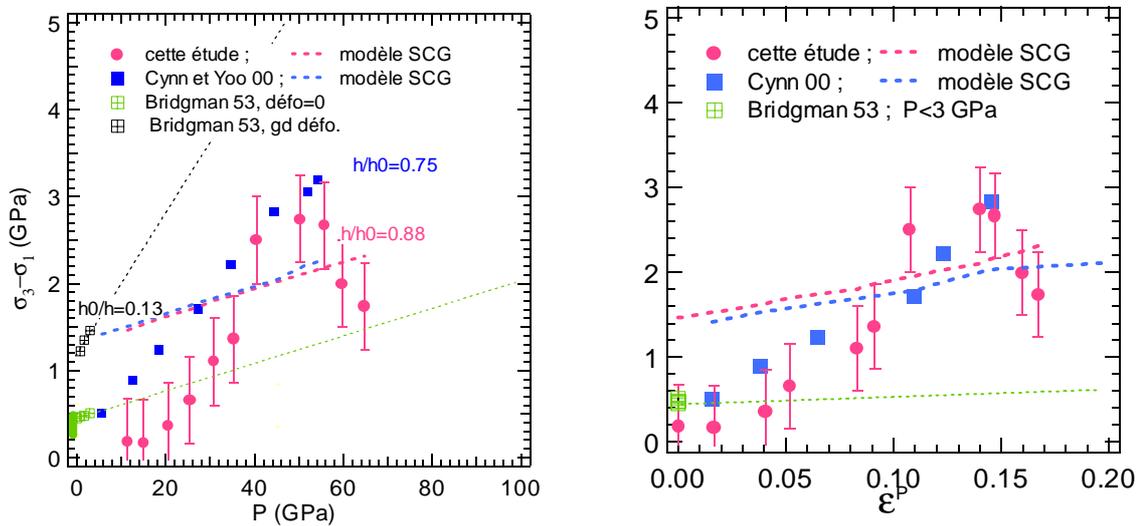
The measured EoS of tantalum is presented on figure 2, together with literature data [1], [2], [3]. The failure of cell 1 diamond, caused by helium diffusion, prevented us from performing hydrostatic measurements for pressures higher than 45 GPa. Measurements performed under non-hydrostatic conditions, after analysis, lead to a compression curve that shows a much smaller scatter than literature data. Third-order Birch Murnaghan EoS fit parameters are the following:  $a_0 = 3.3034 \text{ \AA}$ ,  $K_0 = 195 \text{ GPa}$ ,  $K'_0 = 3.03$ , where these parameters are the lattice parameter, incompressibility and its pressure derivative in the reference state. The  $K'_0$  obtained is lower than the parameter obtained by the most recent study results [1]:  $K'_0 = 3.4$ . This low value has to be confirmed by higher pressure compression experiments.



**Figure 1 (left):** evolution of  $ahkl=dhkl*\sqrt{(h^2+k^2+l^2)}$  for several planes as a function of pressure (ruby fluorescence gauge) in cell 2.

**Figure 2 (right):** measured hydrostatic equation of state, compared with literature data.

### (1) Evolution of yield stress with pressure to 65 GPa:



**Figure 3:** evolution of  $\tau=\sigma_3-\sigma_1$  with plastic pressure and plastic strain. Literature data, see [4] and [5]

In our experiments, the yield stress depends mainly on the amount of plastic deformation  $\epsilon^P$  (hardening) and the hydrostatic pressure. The evolution of  $\tau=\sigma_3-\sigma_1$  with these parameters is plotted in figure 3. The main comments are:

- the large hydrostatic pressure effect on the yield stress (more dramatic than the scaling law  $\tau$  proportional to shear modulus, called SCG model on the figure), observed for the first time on a single crystal
- the good coherence of our measurements with those performed on polycrystal tantalum by an other method [4], which shows that intergranular plasticity seems negligible in that metal.
- the possibility of a decrease of yield stress under ultrahigh pressure, that must be confirmed by higher pressure measurements.

### References:

- [1] H. Cynn and C.-S. Yoo, Phys. Rev. B, 59, 8526-8529 (1999)
- [2] J. Xu et al., High Temp.-High Press., 16, 495, (1984)
- [3] L.Ming and M.H. Manghnani, J. Appl. Phys., 49, 1, 208-212 (1978)
- [4] H. Cynn and C.-S. Yoo, to be published in Phys. Rev. B (2000)
- [5] P.W. Bridgman, J. Appl. Phys., 24, 5, 560-570 (1953)